

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|---|------------------|---------|------------------|
| L1 | 15 | (mask same interfeat\$4) and layer | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:50 |
| L2 | 4607 | (mask same inspect\$4) and layer | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:50 |
| L3 | 2 | (mask same inspect\$4) and layer and interfeat\$4 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:54 |
| L4 | 321 | (mask same inspect\$4) and layer and opc | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:56 |
| L5 | 97 | (mask same inspect\$4) and layer and opc and relationship | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:56 |
| L6 | 92 | (mask same inspect\$4) and layer and opc and relationship and feature | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:57 |
| L7 | 75 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 09:57 |
| L8 | 70 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 10:08 |

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|-----|----|--|--|----|----|------------------|
| L9 | 49 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 10:15 |
| L10 | 31 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 10:32 |
| L11 | 31 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4 and data | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 10:35 |
| L12 | 14 | (mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4 and data and criteria | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/16 10:35 |

| | Document ID | Issue Date | Title |
|----|-------------------|------------|--|
| 1 | US 20050076316 A1 | 20050407 | Design-manufacturing interface via a unified model |
| 2 | US 20050060680 A1 | 20050317 | Rule based system and method for automatically generating photomask orders in a specified order format |
| 3 | US 20050055659 A1 | 20050310 | Rule based system and method for automatically generating photomask orders by conditioning information from a customer's computer system |
| 4 | US 20040133369 A1 | 20040708 | Method and system for context-specific mask inspection |
| 5 | US 20040107412 A1 | 20040603 | Method and system for context-specific mask writing |
| 6 | US 20040025137 A1 | 20040205 | Rule based system and method for automatically generating photomask orders in a specified order format |
| 7 | US 20030126581 A1 | 20030703 | User interface for a network-based mask defect printability analysis system |
| 8 | US 20030088847 A1 | 20030508 | Method of incorporating lens aberration information into various process flows |
| 9 | US 20020026626 A1 | 20020228 | Optical proximity correction |
| 10 | US 6880135 B2 | 20050412 | Method of incorporating lens aberration information into various process flows |
| 11 | US 6842881 B2 | 20050111 | Rule based system and method for automatically generating photomask orders in a specified order format |
| 12 | US 6634018 B2 | 20031014 | Optical proximity correction |
| 13 | US 6578188 B1 | 20030610 | Method and apparatus for a network-based mask defect printability analysis system |
| 14 | US 5657235 A | 19970812 | Continuous scale optical proximity correction by mask maker dose modulation |